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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/707,628	12/25/2003	Jeng-Ywan Jeng	11377-US-PA	1627
31561	7590	02/16/2005	EXAMINER	
JIANQ CHYUN INTELLECTUAL PROPERTY OFFICE 7 FLOOR-1, NO. 100 ROOSEVELT ROAD, SECTION 2 TAIPEI, 100 TAIWAN			NGUYEN, HUNG	
			ART UNIT	PAPER NUMBER
			2851	

DATE MAILED: 02/16/2005

Please find below and/or attached an Office communication concerning this application or proceeding.

Office Action Summary

Application No.

10/707,628

Applicant(s)

JENG ET AL.

Examiner

Hung Henry V. Nguyen

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-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address --

Period for Reply

A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) FROM THE MAILING DATE OF THIS COMMUNICATION.

- Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.
- If the period for reply specified above is less than thirty (30) days, a reply within the statutory minimum of thirty (30) days will be considered timely.
- If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication.
- Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).

Status

- 1) ☒ Responsive to communication(s) filed on 03 February 2005.
- 2a) ☐ This action is **FINAL**. 2b) ☒ This action is non-final.
- 3) ☐ Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under *Ex parte Quayle*, 1935 C.D. 11, 453 O.G. 213.

Disposition of Claims

- 4) ☒ Claim(s) 1-3 is/are pending in the application.
- 4a) Of the above claim(s) _____ is/are withdrawn from consideration.
- 5) ☐ Claim(s) _____ is/are allowed.
- 6) ☒ Claim(s) 1-3 is/are rejected.
- 7) ☐ Claim(s) _____ is/are objected to.
- 8) ☐ Claim(s) _____ are subject to restriction and/or election requirement.

Application Papers

- 9) ☐ The specification is objected to by the Examiner.
- 10) ☒ The drawing(s) filed on 25 December 2003 is/are: a) ☒ accepted or b) ☐ objected to by the Examiner.
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).
- 11) ☐ The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.

Priority under 35 U.S.C. § 119

- 12) ☒ Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).
- a) ☒ All b) ☐ Some * c) ☐ None of:
1. ☒ Certified copies of the priority documents have been received.
2. ☐ Certified copies of the priority documents have been received in Application No. _____.
3. ☐ Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).
- * See the attached detailed Office action for a list of the certified copies not received.

Attachment(s)

- 1) ☒ Notice of References Cited (PTO-892)
- 2) ☐ Notice of Draftsperson's Patent Drawing Review (PTO-948)
- 3) ☐ Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08)
Paper No(s)/Mail Date _____.
- 4) ☐ Interview Summary (PTO-413)
Paper No(s)/Mail Date. _____.
- 5) ☐ Notice of Informal Patent Application (PTO-152)
- 6) ☐ Other: _____.

DETAILED ACTION

Election/Restrictions

1. Applicant's election without traverse of claims 1-3(group I) in the reply filed on February 3, 2005 is acknowledged.

Abstract

2. The abstract of the disclosure is objected to because: on line 1, reference to "comprises" should be --includes--; on line 3, reference to "disposedover" should read -- disposed over-- and on line 10, reference to "bereduced" should read --be reduced--. Correction is required. See MPEP § 608.01(b).

Claim Rejections - 35 USC § 102

3. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless –

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

4. Claims 1-3 are rejected under 35 U.S.C. 102(b) as being anticipated by Liu (U.S.Pat. 5,105,215).

With respect to claim 1, Liu discloses a dynamic mask module (60) adapted to transfer a mask pattern to a photoresist (66) on a substrate (62) and comprising all basic features of the instant claim such as: a microcomputer system (50); a mask pattern generator (30) deposited over the substrate (62) and electrically connected to the microcomputer system for transmitting an image signal of the mask pattern to the mask pattern generator for generating a plurality of

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opaque areas and transparent areas and outputting the mask pattern (see co;4, lines10-17); and a light source (12) disposed over the mask pattern generator (30), light of light source projecting on the opaque areas and transparent areas for transferring the mask pattern onto the photo-resist.

As to claim 2, Liu teaches a focusing lens (40) disposed between the mask pattern generator and the substrate (60) adapted to minify or magnify the mask pattern.

As to claim 3, Liu further teaches the mask pattern generator being a Transmissive LCD or a DLP optical projector (see figure 2; col.4, lines 55-56).

5. Claims 1-2 are rejected under 35 U.S.C. 102(b) as being anticipated by Lin (U.S.Pat. 6,121,626).

With respect to claim 1, Lin discloses a dynamic mask module (TM) adapted to transfer a mask pattern to a photoresist on a substrate (W) (see col.3, lines 61-67) and comprising all basic features of the instant claim such as: a microcomputer system (26); a mask pattern generator disposed over the substrate and electrically connected to the microcomputer system via a control line (32) for transmitting an image signal of the mask pattern to the mask pattern generator for generating a plurality of opaque areas and transparent areas and outputting the mask pattern (see figure 1; col.4, lines 4-32); and a light source (see col.3, lines 1-6) disposed over the mask pattern generator, light of light source projecting on the opaque areas and transparent areas for transferring the mask pattern onto the photo-resist.

As to claim 2, Lin teaches a focusing lens (PLC) disposed between the mask pattern generator and the substrate (W) adapted to minify or magnify the mask pattern.

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Prior Art Made of Record

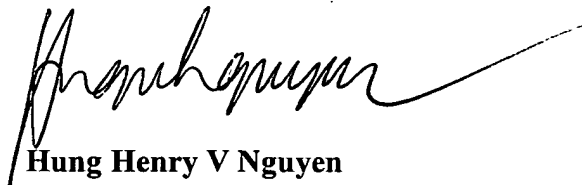
6. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure.

Stein (U.S.pat. 3,824,604) discloses a liquid crystal programmable printing system.

7. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Hung Henry V. Nguyen whose telephone number is 571-272-2124. The examiner can normally be reached on Monday-Friday (First Friday off).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Judy Nguyen can be reached on 571-272-2258. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).



Hung Henry V Nguyen
Primary Examiner
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hmv
2/10/05